



SDI Review Form 1.6

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| Journal Name: | Physical Science International Journal |
| Manuscript Number: | Ms_PSIJ_29024 |
| Title of the Manuscript: | Influence of Annealing Temperature on the Physical Properties of Polycrystalline Cu ₂ SnSe ₃ Thin Films Prepared by Thermal Vacuum Evaporation Technique |
| Type of the Article | Original Research Article |

General guideline for Peer Review process:

This journal's peer review policy states that **NO** manuscript should be rejected only on the basis of '**lack of Novelty**', provided the manuscript is scientifically robust and technically sound.

To know the complete guideline for Peer Review process, reviewers are requested to visit this link:

(<http://www.sciencedomain.org/page.php?id=sdi-general-editorial-policy#Peer-Review-Guideline>)



SDI Review Form 1.6

PART 1: Review Comments

| | Reviewer's comment | Author's comment (if agreed with reviewer, correct the manuscript and highlight that part in the manuscript. It is mandatory that authors should write his/her feedback here) |
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| Compulsory REVISION comments | <p>❖ Title: "Influence of Annealing Temperature on the Physical Properties of Polycrystalline Cu₂SnSe₃ Thin Films Prepared by Thermal Vacuum Evaporation Technique" change to "Influence of Annealing Temperature on the Physical Properties of Cu₂SnSe₃ Thin Films Prepared by Thermal Vacuum Evaporation Technique".</p> <p>If authors like to keep their interpretation, they must bring the details of the Cu₂SnSe₃ Thin Films they used ("ref of bulk Cu₂SnSe₃" or "Spectre DRX" with JCPDS or ICSD file numbers).</p> <p>❖ Section Abstract, Line 8) "p-type semiconductor". Specify the method you used to confirm and please do not forget to add it in the text.</p> <p>❖ Section 3.2 Energy Dispersive X-Ray Analysis (EDX), Line 6) "Figure 5.26?" change to "Figure 3".</p> <p>❖ Section 3.2 Energy Dispersive X-Ray Analysis (EDX), Title of Figure 3) "Figure 3: EDX spectrum of Cu₂SnSe₃ thin films annealed at 500 °C." change to "Figure 3: EDX spectrum of Cu₂SnSe₃ thin films as-</p> | <p>Title changed to "Influence of Annealing Temperature on the Physical Properties of Cu₂SnSe₃ Thin Films Prepared by Thermal Vacuum Evaporation Technique".</p> <p>In prior time, we have investigated the type of semiconductor earlier and publish the result at different kind of journal. Authors agreed there is no issue to confirm the semiconductor type because it is easy to find it in other journal.</p> <p>"Figure 5.26?" changed to "Figure 3".</p> <p>Figure 3 changed to "Figure 3: EDX spectrum of Cu₂SnSe₃ thin films as-deposited and annealed (at 100, 200, 300, 400 and 500 °C)."</p> <p>Thickness of the thin films measured using XP-Plus Stylus Profiler XP-200 Surface Profiler in room temperature</p> |



SDI Review Form 1.6

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| | <p>deposited and annealed (at 100, 200, 300, 400 and 500 °C).”</p> <p>❖ How did you calculate the thickness for the deferent annealing temperatures?</p> <p>In addition to that:</p> <ul style="list-style-type: none"> - First: See sections 3.3 I-V Characteristics, Please correct the design of figure 6. - Secondly: See section 3.4 Electrical Resistivity and Conductivity, Please add the thickness (d) and the sheet resistance (R_s) in table 2. - Third: please go to figure 7 and correct the symbol, instead of (Ω) you replace by electrical conductivity (σ). <p>❖ On the other hand I notice that the reference [15] did not exist in the text.</p> | <p>conditions. Figure 6 axis title corrected.</p> <p>Thickness and sheet resistance were not added to the table.</p> <p>Nothing wrong with the figure because both graph electrical resistivity and electrical conductivity were combined into one figure. Reference [15] belongs to ref. [14]. Original ref. [14] removed.</p> |
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| <u>Minor</u> REVISION comments | <ul style="list-style-type: none">❖ Section Abstract, Line 5) "Van der Pauw" change to "Van Der Pauw".❖ Section Abstract, Line 9) "from I-V characteristic analysis" rephrase.❖ Section 1. INTRODUCTION, Line 9) "mixed phase" change to "mixed phases".❖ Section 1. INTRODUCTION, Line 9) "space group P n m a" change to "space group Pnma".❖ Section 1. INTRODUCTION, Line 13) "electrodeless" change to "electroless" or "electrodeposition". Please do not forget to add a reference. | |
| <u>Optional/General</u> comments | <ul style="list-style-type: none">❖ Specify the thickness and time of different annealing temperatures?❖ In my opinion, can you remove figure 1 or figure 2 because the comparaisn for this study is not clear. | |